

# The Property of Adhesion and Biocompatibility of Silicon and Fluorine Doped Amorphous Carbon Films

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## About our Study

In this study, we developed **silicon and fluorine doped amorphous carbon (a-C:H:Si:F) film** using radio frequency plasma enhanced chemical vapor deposition (RF-PECVD) method, which exhibits both **high adhesion** of silicon-incorporated interlayer and **excellent biocompatibility** of fluorine doped amorphous carbon (a-C:H:F) film (**Fig. 1**), aiming at shortening the film deposition time. In order to fabricate a-C:H:Si:F film and realize the good property, the mixture of TMS, C<sub>3</sub>F<sub>8</sub> and C<sub>2</sub>H<sub>2</sub> gases was used for depositon (**Table. 1**), and the adhesion property and biocompatibility were evaluated.

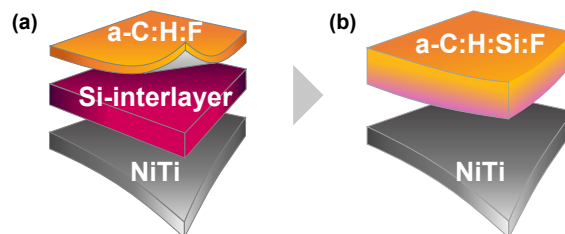


Fig. 1 Film structure images of (a) a-C:H:F with Si-interlayer and (b) a-C:H:Si:F

Table. 1 Deposition parameters of a-C:H:Si:F films

Sample name	bias (kV)	source gas flow late (sccm)		
		TMS	C <sub>3</sub> F <sub>8</sub>	C <sub>2</sub> H <sub>2</sub>
no-gradation	-1.5	6	50	0
F-gradation	-1.5	6	0→50	0
Si,F-gradation	-1.5	6→1	0→50	0
C <sub>2</sub> H <sub>2</sub> -doped	-1.5	6→0	0→50	0→3

## Results and Discussion

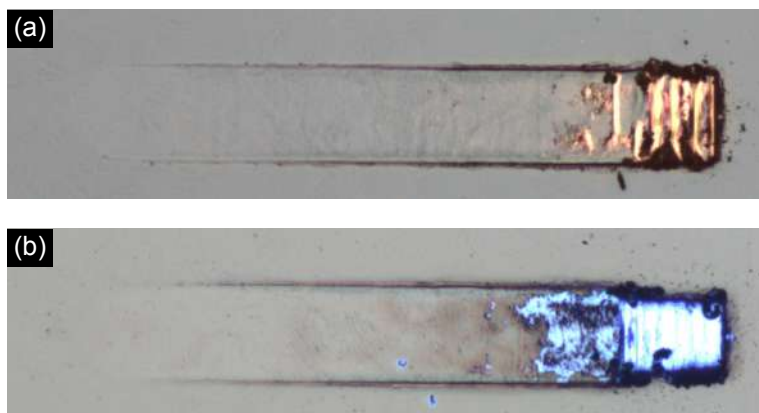


Fig. 2 The scratch traces of (a) C<sub>2</sub>H<sub>2</sub>-doped and (b) a-C:H:F with Si-interlayer

### Evaluation of Adhesion

In this study, “no-gradation” was firstly deposited, but this showed low adhesion property. Thus, we newly developed a-C:H:Si:F films at a gas flow rate of gradually changed. In **Fig. 2**, the scratch traces of “C<sub>2</sub>H<sub>2</sub>-doped”, which is one of the gradation films, and a-C:H:F with Si-interlayer after the scratch test are shown. “C<sub>2</sub>H<sub>2</sub>-doped” exhibited higher adhesion property than a-C:H:F with Si-interlayer, because “C<sub>2</sub>H<sub>2</sub>-doped” was deposited in one process and had no low adhesion interface.

### Evaluation of Biocompatibility

Platelet adhesion test and leukocyte adhesion test were conducted in order to evaluate biocompatibility of the “C<sub>2</sub>H<sub>2</sub>-doped” a-C:H:Si:F film and a-C:H:F with Si-interlayer. These two coatings were found to significantly reduce the number of adherent platelets (**Fig. 3**) and leukocytes (**Fig. 4**) compared with non-coated NiTi substrate, and exhibited the same number of them.

These results shows that C<sub>2</sub>H<sub>2</sub>-doped has the same biocompatibility as a-C:H:F, and means that these two films have similar chemical composition, bonding state and surface free energy.

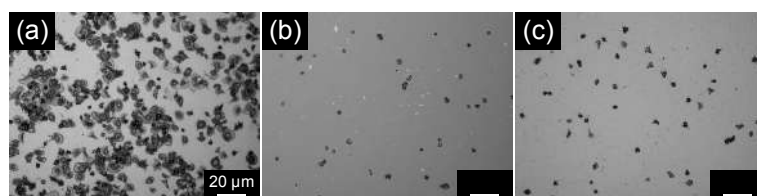


Fig. 3 Images of adherent platelets on each sample : (a) NiTi substrate, (b) C<sub>2</sub>H<sub>2</sub>-doped, (c) a-C:H:F with Si-interlayer



Fig. 4 Images of adherent leukocytes on each sample : (a) NiTi substrate, (b) C<sub>2</sub>H<sub>2</sub>-doped, (c) a-C:H:F with Si-interlayer